

Controlled self-organized positioning of small aggregates by patterns of (sub)nano-size active sites

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Supporting Information

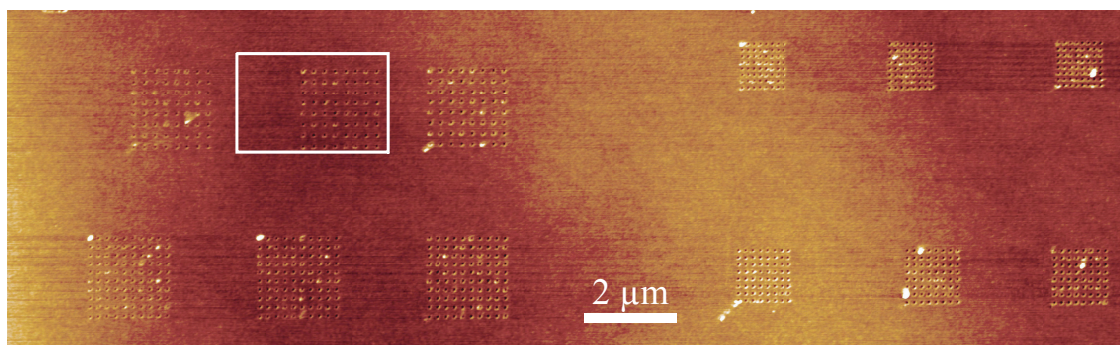


Figure S1: Substrate area with twelve arrays of dents with different inter-dent spacings. The image was taken right after preparation prior to cleaning. The array singled out by the white frame is the one from Figure 1 of the article.

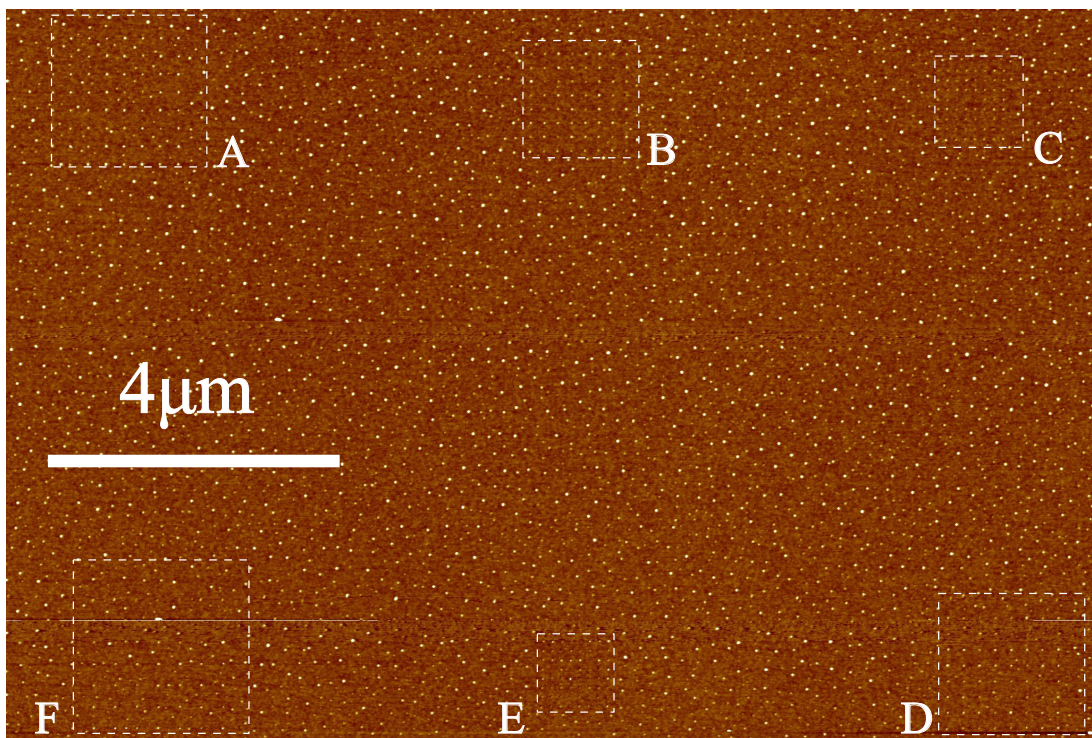


Figure S2: Substrate area with six arrays of dents after deposition of the C_{60} . The location of the dent arrays is indicated by the white rectangles. The spacings between the dents in the various arrays are: A) 250 nm, B) 190 nm, C) 130 nm, D) 220 nm, E) 130 nm, and F) 300 nm. The vertical force for the preparation of the dents was $7.5 \mu\text{N}$ for arrays A, B and C, For arrays D, E and F it was $5.5 \mu\text{N}$.